

# Chemical Vapor Deposition

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## AME P5000 Chamber A

- Used for PECVD Deposition of TEOS Oxide

## AME P5000 Chamber B

- Used for PECVD Deposition of TEOS Oxide on contamination threat substrates

## ASM LPCVD Tube 1

- Used for LPCVD deposition of low temperature oxide

## ASM LPCVD Tube 2

- Used for LPCVD deposition of polysilicon and silicon nitride

## Ultratech S200 ALD

- Deposition of atomic layer films

## Other Information

[SMFL CVD Process Information](#)

[Good overview of CVD Processes](#)